

Docket No. 2001-0108-1
USPN 10/036,925

IN THE CLAIMS:

Please amend Claim 1 as follows:

1. (Amended) A process for providing lithographic exposures utilizing a line narrowed gas discharge laser, comprising the steps of:

- A. modeling with a computer program lithographic parameters to determine a desired laser spectrum needed to produce a desired lithographic result,
- B. utilizing a fast responding tuning mechanism to adjust center wavelength of laser pulses in a burst of pulses to achieve an integrated spectrum for the burst of pulses approximating the desired laser spectrum.

Conclusion

For the above reasons the claims as amended should be allowable and Applicants request that they be allowed and the above-identified application allowed to issue as a patent.

Applicants do not believe any fees are due in connection with this submission however, if fees are due, the Commissioner is authorized to charge our Deposit Account No. 03-4060 the appropriate amount.

Marked Up Copy

Applicants have attached marked up copy of earlier versions of claim 1 showing the change made of the claim as now amended.

Respectfully submitted,


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